2022년 1월 26일(수), 09:00-10:30
Room C (사파이어 I, 5층)

## Q. Metrology, Inspection, Analysis, and Yield Enhancement 분과
## [WC1-Q] Metrology, Inspection, and Yield Enhancement I

좌장: 정용우 TL(SK 하이닉스), 강상우 소장(KRISS)

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| **WC1-Q-1**<br>**09:00-09:30** | **Spatially, Temporally, and Spectrally Resolved Thermal Imaging Microscopy and Semiconductor Applications**<br>장기수, 김동욱, 정찬배, 김정대, 한일규<br>*한국기초과학지원연구원 연구장비개발부* |
| **WC1-Q-2**<br>**09:30-09:45** | **반도체 패키지 계면 상태 진단을 위한 동적 열특성 기반 비파괴 분석 기술**<br>마병진, 정태희, 최성순, 이관훈<br>*한국전자기술연구원* |
| **WC1-Q-3**<br>**09:45-10:00** | **The Faster Method to Identify the Yield Detractor by the Automated Analysis Using Volume Diagnosis Result**<br>Baekkwon Choi[1], Jeongsu Park[2], Hyungki Kim[1], Sangjin Park[1], Junghyun Choi[1], Junwan Park[2], and Brad Kim[2]<br>*[1]SK Hynix, [2]Synopsys Korea* |
| **WC1-Q-4**<br>**10:00-10:15** | **Optical Characterization Equipment for Manufacturing Processes of Si Semiconductor Device**<br>YoungMin Park[1], HyunDon Jung[1], DongHan Kim[1], DongHyun Jang[1], YongHee Jeon[1], GyuHyeong Cho[1], Sung-Jin Chang[2], Woo Sik Soun[2], Chil Seong Jeong[2], Jong-Bum You[2], Jin Su Kim[2], and Jun-Mo Yang[2]<br>*[1]Etamax Co., Ltd., [2]National Nanofab Center* |
| **WC1-Q-5**<br>**10:15-10:30** | **Development of A Real-Time Contamination Particle Sensor with Sampling and Anti-Contamination Module to Measure in Various Process Environments**<br>Jongho kim[1,2], Jihun Mun[1], and Sang-Woo Kang[1,2]<br>*[1]KRISS, [2]UST* |